

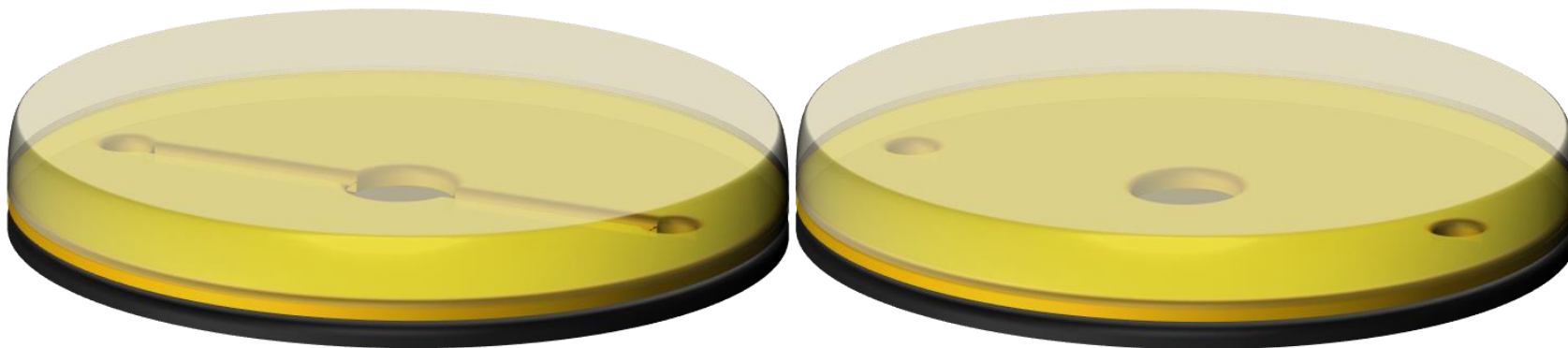
A

Spincoat SU-8 on
silicon wafer

B

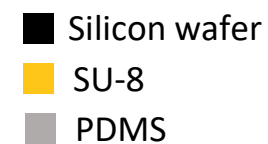
Pre-exposure bake.
Apply photomask.

UV exposure

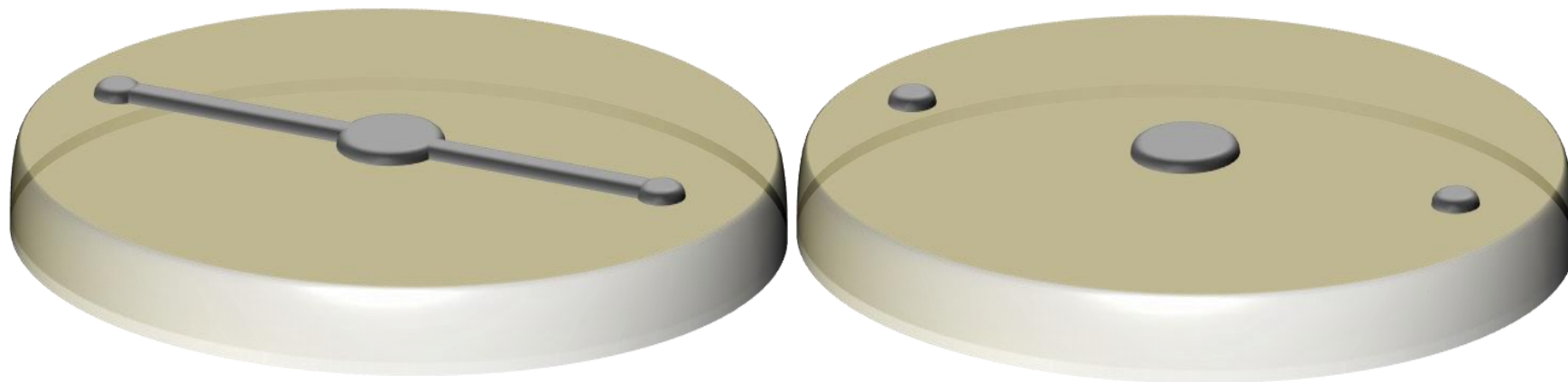
C

Post-exposure bake.
Develop photoresist.

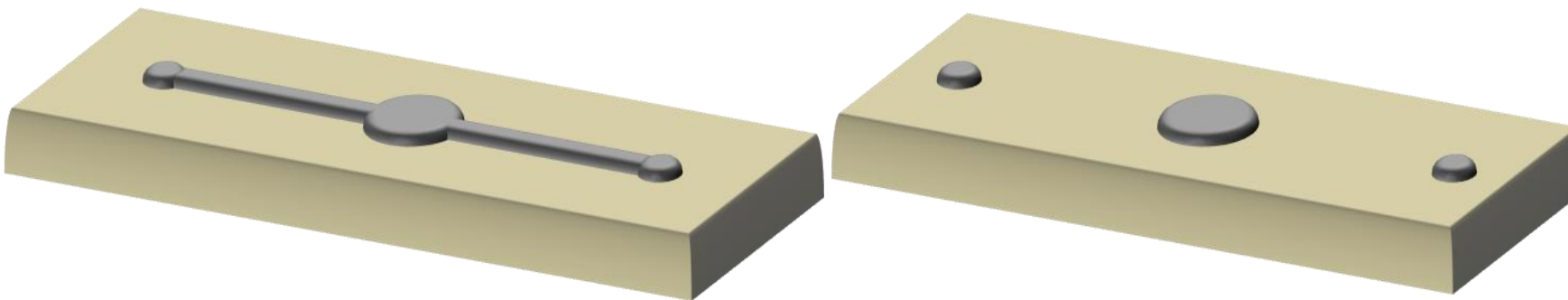
Apply PDMS on
SU-8 master



D



E

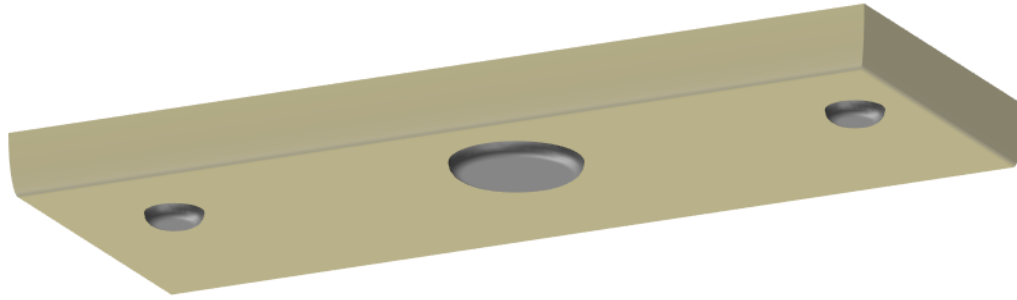


Peel of PDMS
molds from SU-8
master

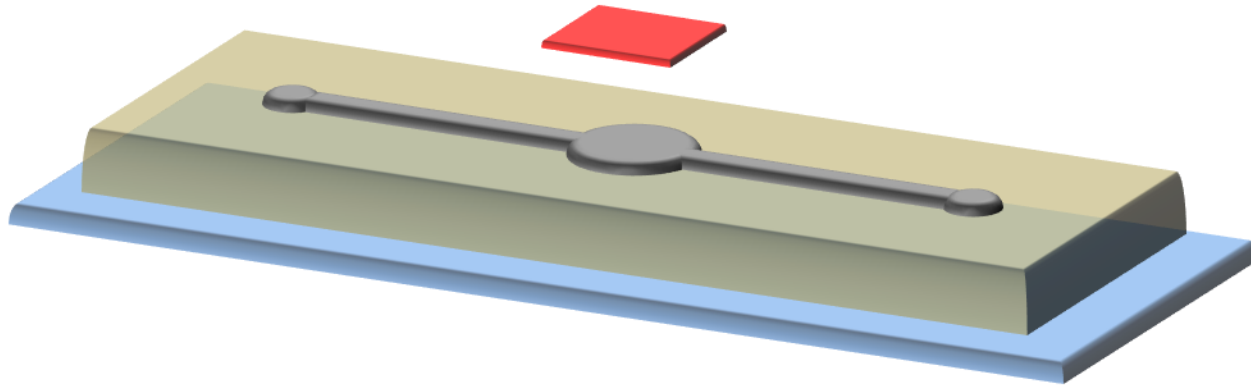


Cut PDMS molds

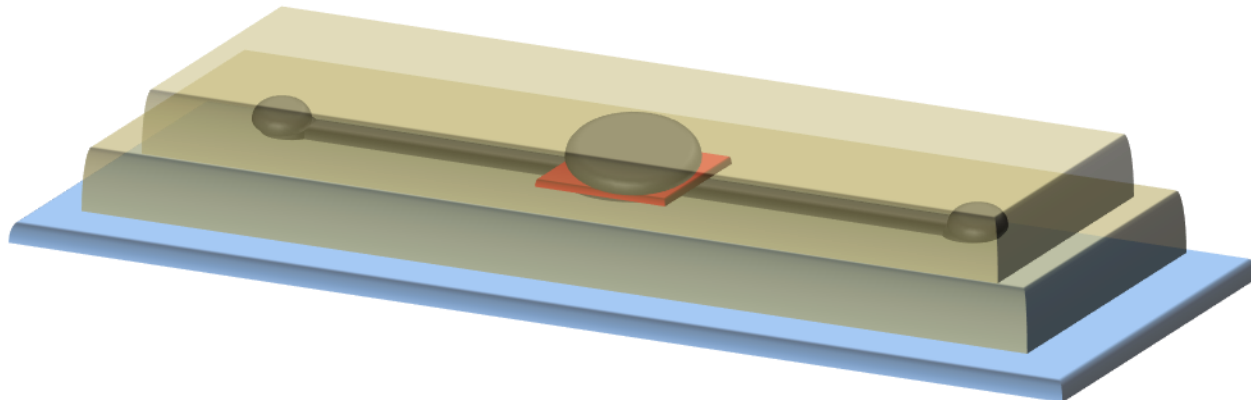
F



Deposit PDMS molds on glass slide. Cut and place RC dialysis membrane in between the central pillars.

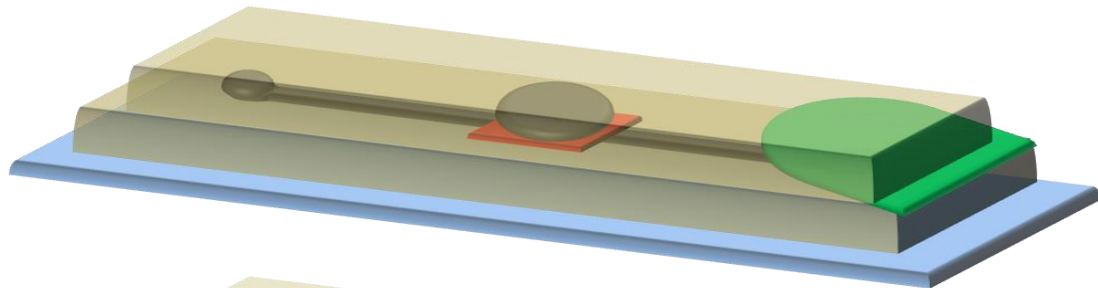


G

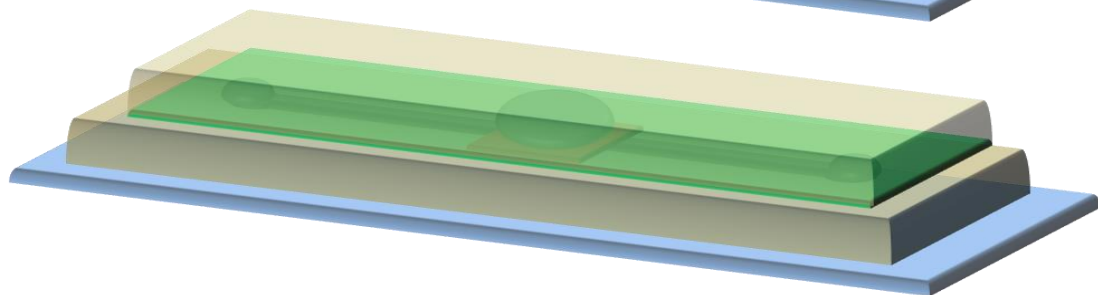


Align and desiccate in vacuum chamber.

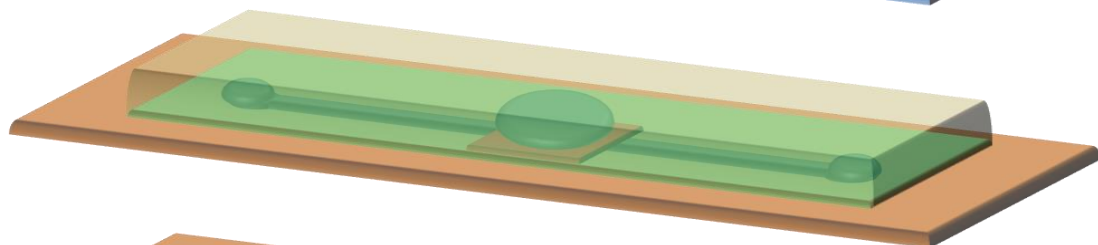
■ Glass slide
■ RC membrane

H

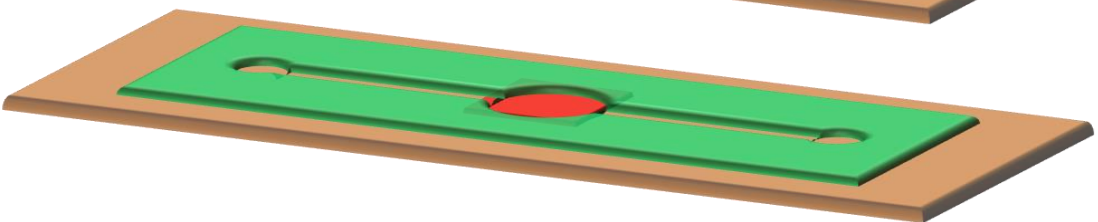
Deposit NOA81 resin.

I

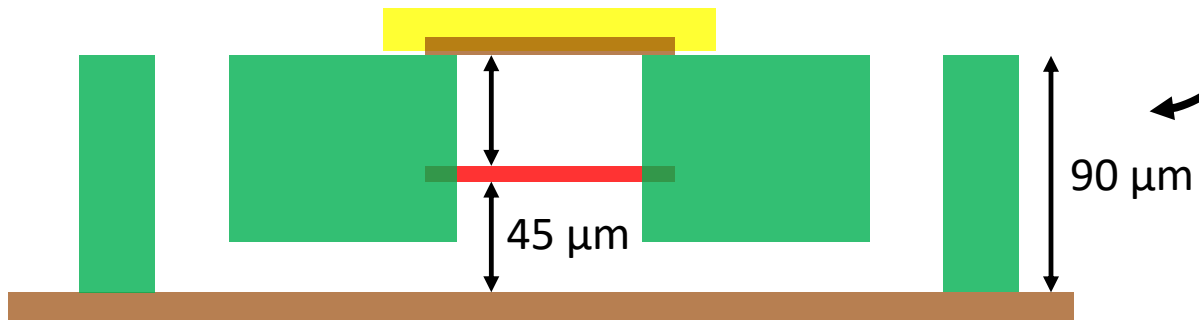
Fill in with NOA81 by capillarity. 1st UV exposure.

J

Remove lower PDMS mold. Deposit on PMMA. 2nd UV exposure.

K

Remove upper PDMS mold.

L

Side view of the dialysis chip.

- | | |
|---|---|
| PMMA (175 μm) | RC membrane (40 μm) |
| NOA81 (90 μm) | Kapton (20 μm) |